



Alfred J. Reich, Ph.D.

Gentleman Scientist
 Mathematics
 Computation
 Artificial Intelligence
 Machine Learning
 Consciousness

	All	Since 2015
Citations	718	87
h-index	13	4
i10-index	15	1

TITLE	CITED BY	YEAR
One dimensional lithographic proximity correction using DRC shape functions AJ Reich, KD Lucas, ME Kling, WD Grobman, BJ Roman US Patent 5,900,340	233	1999
Process for producing and inspecting a lithographic reticle and fabricating semiconductor devices using same KD Lucas, ME Kling, AJ Reich, CC Fu, J Morrow US Patent 5,849,440	72	1998
Polarized phase shift mask: concept, design, and potential advantages to photolithography process and physical design R Wang, WD Grobman, AJ Reich, MA Thompson 21st Annual BACUS Symposium on Photomask Technology 4562, 406-417	68	2002
Practicing extension of 248-nm DUV optical lithography using trim-mask PSM ME Kling, N Cave, BJ Falch, CC Fu, KG Green, KD Lucas, BJ Roman, ... Optical Microlithography XII 3679, 10-17	56	1999
Two dimensional lithographic proximity correction using DRC shape functions AJ Reich, WD Grobman, BJ Roman, KD Lucas, CH Browning, ME Kling US Patent 5,920,487	45	1999
Lithographic proximity correction through subset feature modification AJ Reich, HL Chuang, ME Kling, PGY Tsui, K Lucas, JN Conner US Patent 5,958,635	40	1999
Shuttle mask floorplanning G Xu, R Tian, MDF Wong, AJ Reich 23rd Annual BACUS Symposium on Photomask Technology 5256, 185-194	30	2003
Methods of designing a reticle and forming a semiconductor device therewith K Lucas, ME Kling, BJ Roman, AJ Reich US Patent 5,827,625	30	1998
Method for adding features to a design layout and process for designing a mask EO Travis, A Dengi, S Chheda, TK Yu, MS Robertson, R Tian, RE Boone, ... US Patent 6,593,226	27	2003
OASIS vs. GDSII stream format efficiency AJ Reich, KH Nakagawa, RE Boone 23rd Annual BACUS Symposium on Photomask Technology 5256, 163-173	25	2003

TITLE	CITED BY	YEAR
Using design intent to qualify and control lithography manufacturing J Vasek, B Wilkinson, D Smith, A Reich, C Garza, J Wiley, J Zhao, ... Mask and Lithography Conference (EMLC), 2006 22nd European, 1-5	14	2006
Method and apparatus for forming a pattern on an integrated circuit using differing exposure characteristics WD Grobman, R Wang, AJ Reich US Patent 6,605,395	13	2003
New stream format: progress report on containing data size explosion P LaCour, AJ Reich, KH Nakagawa, SF Schulze, L Grodd Design and Process Integration for Microelectronic Manufacturing 5042, 214-221	13	2003
Intervals, Points, and Branching Time AJ Reich Time-94: An International Workshop on Temporal Representation and Reasoning	12	1994
0.25-um logic manufacturability using practical 2D optical proximity correction ME Kling, KD Lucas, AJ Reich, BJ Roman, H Chuang, PV Gilbert, ... Optical Microlithography XI 3334, 204-214	11	1998
GDSII considered harmful AJ Reich, RE Boone, WD Grobman, C Browning 21st Annual BACUS Symposium on Photomask Technology 4562, 171-182	8	2002
An efficient representation of spatial data for terrain reasoning by computer generated forces AJ Reich ELECSIM 95-Electronic Conference on Scalability in Training Simulation. Held ...	8	1995
Dummy Feature Placement for Oxide Chemical-Mechanical Polishing Manufacturability R Tian, DF Wong, R Boone, A Reich Proc. Design Automation Conf	7	1999
Predicting computer resource usage AJ Reich, CM Yuan, RE Boone 24th Annual BACUS Symposium on Photomask Technology 5567, 372-381	5	2004
Overview of reticle enhancement technology software strategy AJ Reich, RD Jarvis, S Talent, R Carter Microlithographic Techniques in Integrated Circuit Fabrication II 4226, 77-82	1	2000
Toward a Framework for Analyzing Large-Scale Networks of Entities and Relations A Reich, D Garcia, N Desai, S Marcus, K Lossau, J Beveridge, L Holloway 2011 MSS National Symposium on Sensor & Data Fusion (NSSDF)		2011
Using Semantic Web Technology to Exploit Soft Information A Reich, J Karakowski, D Haug, D Garcia 2009 MSS National Symposium on Sensor & Data Fusion (NSSDF)		2009

TITLE	CITED BY	YEAR
Cost of ownership reduction for OPC development and production CM Yuan, B Jarvis, KD Lucas, R Boone, R Tian, A Reich Optical Microlithography XVII 5377, 1121-1129		2004
Practical quality metrics for resolution enhancement software RE Boone, K Lucas, R Wynd, M Boatright, MA Thompson, AJ Reich Cost and Performance in Integrated Circuit Creation 5043, 162-171		2003
Combat Planning via Battle Simulation AJ Reich, L Rebbapragada 1995 Symposium on Command and Control Research and Technology		1995
Avenue of Approach Generation using a Topological Model of Terrain The Third Workshop on Battlefield Intelligence for AirLand Operations		1992
An Adaptive Asymptotically Efficient Multivariate Estimator of Location A Reich Conference on Applied Analysis (Mathematics and Statistics) in Aerospace ...		1985
Tracking and Data Relay Satellite (TDRS) / Shuttle Tracking Geometry A Reich American Institute of Aeronautics and Astronautics (AIAA) Annual Symposium		1985
Estimating Inertial Measurement Unit Errors on the Pad A Reich American Institute of Aeronautics and Astronautics (AIAA) Annual Symposium		1982